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| U.S. PATENT DOCUMENTS  |              |          |                                |                                   |            |                      |  |
| EXAMINER INITIALS  | DOCUMENT NO. | DATE     | NAME                           | CLASS                             | SUBCLASS   | FILING DATE IF APPR. |  |
| GT   | 4,256,828    | 3/17/81  | George H. Smith                | 430                               | 280.1      |                      |  |
| GT   | 4,882,245    | 11/21/89 | Jeffrey D. Gelorme, et al.     | 430                               | 280.1      |                      |  |
| GT   | 4,940,651    | 7/10/90  | Lawrence M. Brown, et al.      | 430                               | 280.1      |                      |  |
| gt   | 5,026,624    | 6/25/91  | Richard A. Day, et al.         | 430                               | 280.1      |                      |  |
| gt   | 5,043,221    | 8/27/91  | Joseph V. Koleske              | 430                               | 913        |                      |  |
| GT   | 5,098,616    | 3/24/92  | Edward D. Babich, et al.       | 430                               | 280.1      |                      |  |
| GT   | 5,102,772    | 4/7/92   | Raymond W. Angelo, et al.      | 430                               | 280.1      |                      |  |
| GT   | 5,278,010    | 1/11/94  | Richard A. Day, et al.         | 430                               | 280.1      |                      |  |
| GT   | 5,304,457    | 4/19/94  | Richard A. Day, et al.         | 430                               | 280.1      |                      |  |
| GT   | 5,859,655    | 1/12/99  | Jeffrey Donald Gelorme, et al. | 204                               | 501        |                      |  |
| FOREIGN PATENT DOCUMENTS   |              |          |                                |                                   |            |                      |  |
| EXAMINER INITIALS  | DOCUMENT NO. | DATE     | COUNTRY                        | CLASS                             | SUBCLASS   | TRANSLATION YES NO   |  |
|  |              |          |                                |                                   |            |                      |  |
|  |              |          |                                |                                   |            |                      |  |
| OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)   |              |          |                                |                                   |            |                      |  |
| gt Crivello et al. "Photoinitiated Catronic Polymerization with Triarylsulfonium Salts", Journal of Polymer Science: Polymer Chemistry Edition, Vol. 17, pp. 977-999 (1979).   |              |          |                                |                                   |            |                      |  |
| gt N. La Branca and J.D. Gelorme, "High Aspect Ratio Resist for Thick Film Applications", Proc. SPIE, Vol. 2438, pp. 846-852 (1995).   |              |          |                                |                                   |            |                      |  |
| gt K.Y. Lee et al., "Micromachining applications of a high resolution ultrathick photoresist", J. Vac. Sci. Technology B 13(6), Nov./Dec. 1995.  |              |          |                                |                                   |            |                      |  |
| gt Sotec Microsystems Photoepoxies Product Brochure  |              |          |                                |                                   |            |                      |  |
| EXAMINER: <i>Christopher Hartman</i>   |              |          |                                | DATE CONSIDERED: 02-9-03          |            |                      |  |
| *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. |              |          |                                |                                   |            |                      |  |